

ATLAS ITk FBK 3D sensors $50 \times 50 \mu\text{m}^2$

In-Pixel local efficiency after irradiation up to $1.9 \times 10^{16} \text{ n}_{\text{eq}} / \text{cm}^2$

G. Calderini, F. Crescioli, G.-F. Dalla Betta, G. Gariano, C. Gemme, S. Hadzic, T. Heim, **S. Ravera**,
M. Ressegotti, A. Rummler, Md. A. A. Samy, D M S Sultan, L. Vannoli

TREDI 2023

18th Trento workshop on Advance Silicon Radiator Detectors

Trento, 28 February - 2 March 2023

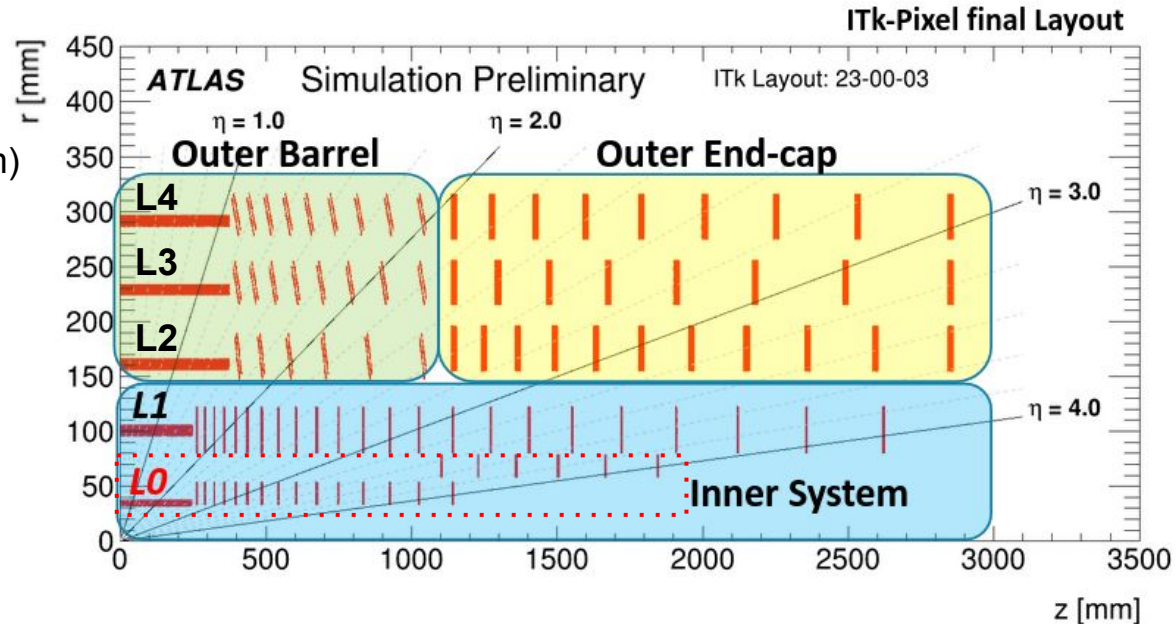


With the HL-LHC program starting in 2026 the **luminosity will ramp up to $5-7.5 \cdot 10^{34} \text{ cm}^{-2} \text{ s}^{-1}$**

- the ATLAS Inner tracker will be completely replaced with a new **all-silicon** (pixel+strip) tracking detector → **The ITk**

The ITk Pixel detector:

- 5 layers of Pixel detectors:
 - L2-L3-L4**: Planar sensors ($150 \mu\text{m}$)
 - L1**: Planar sensors ($100 \mu\text{m}$)
 - L0**: **3D sensors**
- Pixel Inner System will be replaced after 2000 fb^{-1} (1.5 safety factor on max fluence)
 - Fluence of about $2e16 \text{ n}_{\text{eq}}/\text{cm}^2$**
 - TID up to 1 Grad**



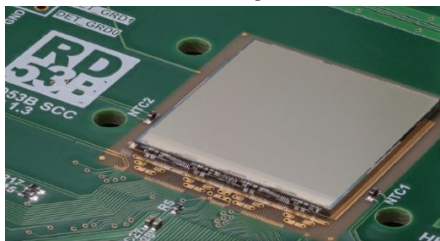
[ITk Final Layout](#)

The ITk Pixel FE Chip: The ITkPix

The ITkPix FE Chip will be used for all ITk modules

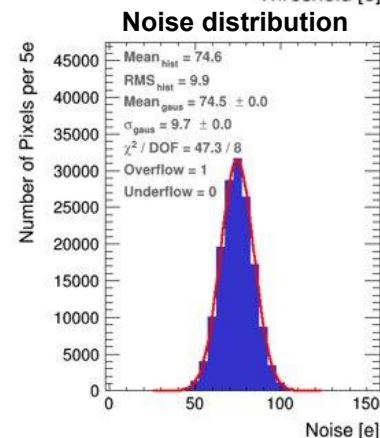
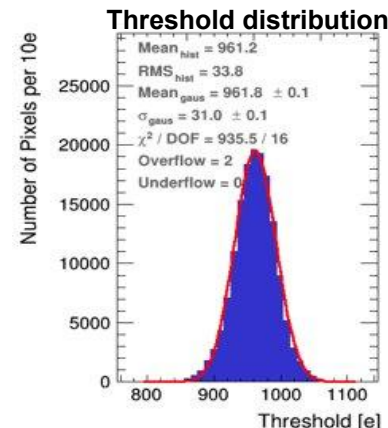
- **Delivered by the RD53 Collaboration**, using the same "library" to finalize the ATLAS and CMS read-out chips
- **ITkPixV1.1** chip: patch fixed high current (**ToT still not usable**)
- **ITkPixV2** chip to be submitted in **Spring 2023** (final simulation ongoing)

ITkPix FE Chip on SCC



Main ITkPixV1 features:

- 65 nm CMOS, 2x2 cm² area
- 384 x 400 pixels (50x50 μm²)
- Power consumption: 0.56 W/cm²
- **Radiation hardness > 1 Grad**
- **Standard threshold: 1000e** (30e dispersion)
- **Mean Noise: 40e (FE only) → 80e after sensor bump-bonding**



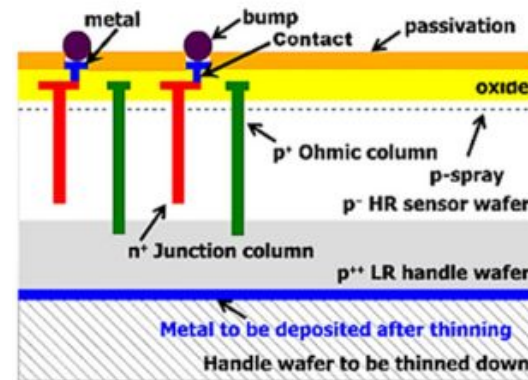
Inner System 3D pixel sensor

ATLAS ITk will use **3D pixels in the Inner System** L0 with 2 different pixel cell dimensions (2x2 cm² tiles):

- 25x100 μm² in the barrel
- 50x50 μm² in the endcaps

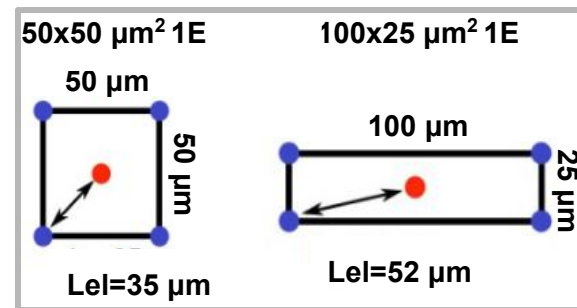
ATLAS Production is split between:

- CNM (25x100 μm², backup FBK)
- FBK and SINTEF (50x50 μm²)



Pre-production almost completed

- by **FBK in Summer 2021** (50x50 μm²) → **Production**
- by FBK in Summer 2022 (25x100 μm²)
- by SINTEF in February 2022 (50x50 μm²)
- CNM expected delivery: March 2023 (25x100 μm²)

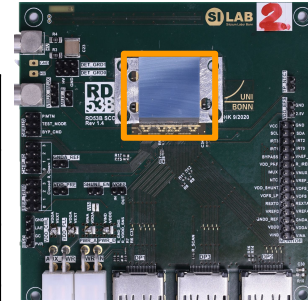


See also [J. Carlotto's talk](#)

Eight 3D + ITkPixV1.1 single-chip modules assembled in Genova on Single Chip Cards (SCCs)

- Bump-bonded at IZM
- Radiation hardness and performance qualification of single chips

Module on SCC

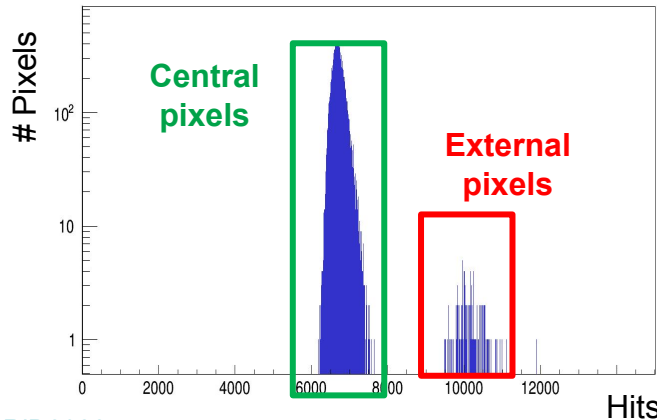
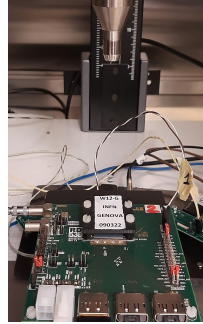
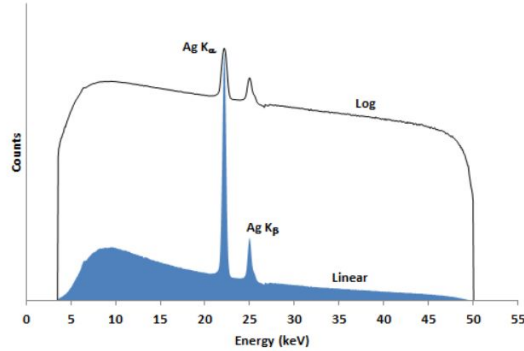


In the following
W12-M → SCC3
W12-J → SCC5

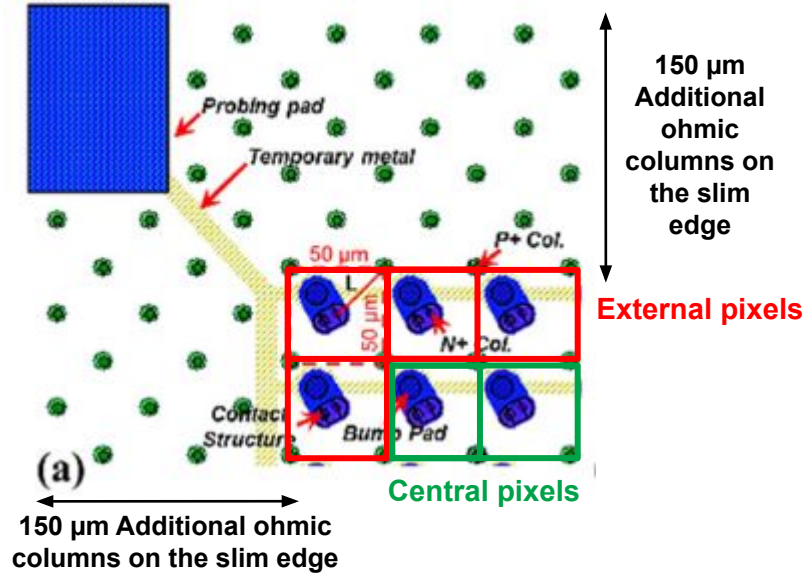
Sensor #	TB before irradiation	Irradiation	Fluence	TB after irradiation	Notes
W12-G	CERN PS & SPS	IRRAD	up to $1.7 \times 10^{16} n_{eq}/cm^2$		Magnet issue at IRRAD → Not able to test after irradiation
W12-M		Bonn + IRRAD	up to $1.9 \times 10^{16} n_{eq}/cm^2$	SPS	
W12-N	CERN PS & SPS				Used as timing reference plane at TBs
W12-J		Bonn + IRRAD	up to $1.9 \times 10^{16} n_{eq}/cm^2$	SPS	
W12-L		CYRIC	$1.5 \times 10^{16} n_{eq}/cm^2$		Irradiation finished on February 2023
W14-K		IRRAD	up to $1.7 \times 10^{16} n_{eq}/cm^2$		Magnet issue at IRRAD → Not able to test after irradiation
W14-H					Serious BB issue
W14-M		CYRIC	$1.5 \times 10^{16} n_{eq}/cm^2$		Irradiation finished on February 2023

Laboratory characterisation

- Source: X-ray tube (Amptek Mini-X2), with Ag anode



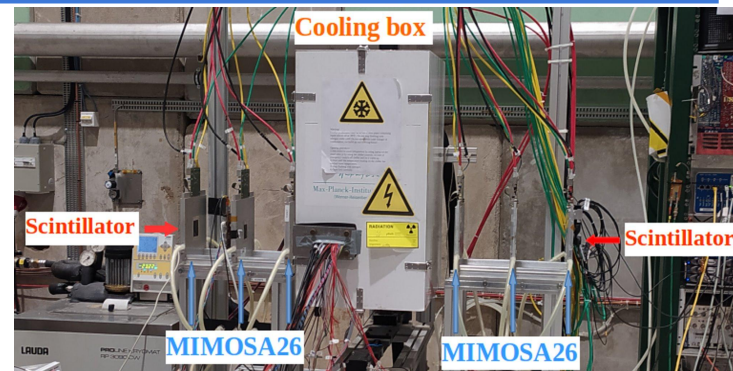
More info here [WORLD2022](#)



- Scans are run in Self-Trigger mode (HitOR)
 - 30% more hits in the external pixels on the slim edge due to extension of the electric field

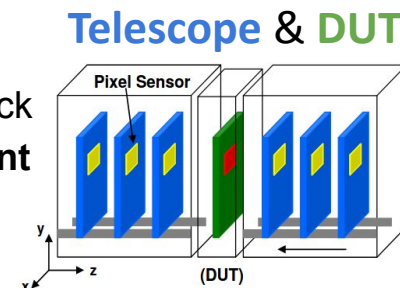
Several TBs 2022 Campaigns

- Proton Synchrotron (PS): April 2022
- Super Proton Synchrotron (SPS): May-July-November 2022
- Data analysed with the C++ based framework [Corryvreckan](#)
- A 6-plane telescope [[MIMOSA26](#)] alignment with track χ^2 minimization \rightarrow $\sim 3 \mu\text{m}$ resolution on track reconstruction

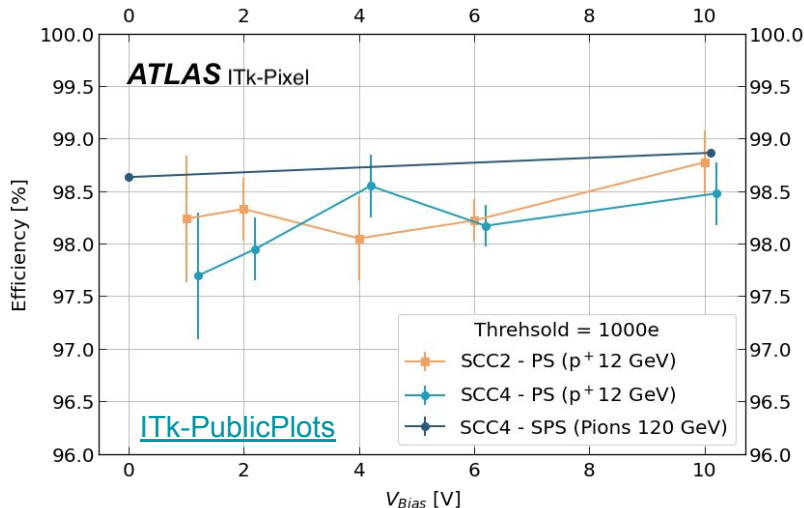


The efficiency is calculated

- with tracks on DUT that **meets spatial and time** cuts w.r.t. reconstructed track
- **disabled, masked pixels and neighbouring ones are not taken in account**
- the resulting efficiency is valid for pixels that are not masked or disabled



Efficiency of unirradiated 3D modules



Unirradiated modules tested at PS and SPS perpendicular to the beam

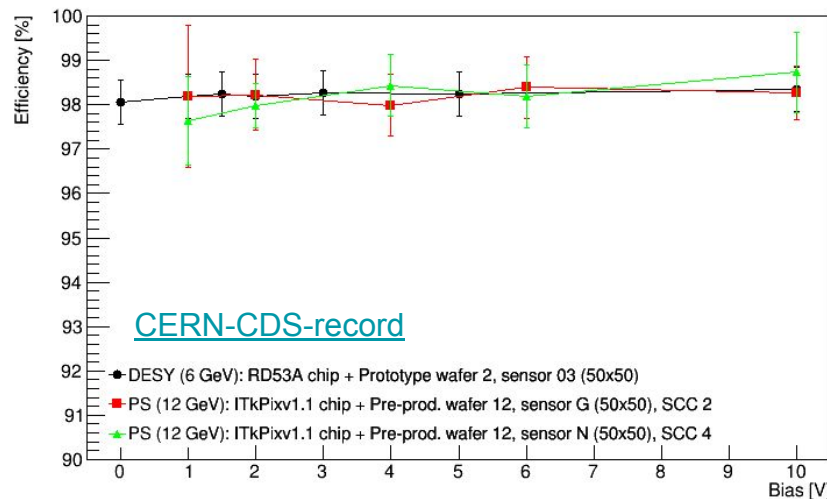
- **Efficiency > 98% already at 0 V bias (unirradiated)**
- PS [12 GeV protons] 1-10 V bias, low statistics, not optimal DAQ
- SPS [120 GeV pions] 0 and 10 V bias, high statistics

SPS proton beam perpendicular to DUT

Sensor average efficiency

- **0 V : 98.7 ± 0.1 %**
- **10 V: 98.9 ± 0.1 %**

Results compatible with $50 \times 50 \mu\text{m}^2$ prototype (RD53A chip + FBK 3D sensor) previously tested at DESY (6 GeV electrons)

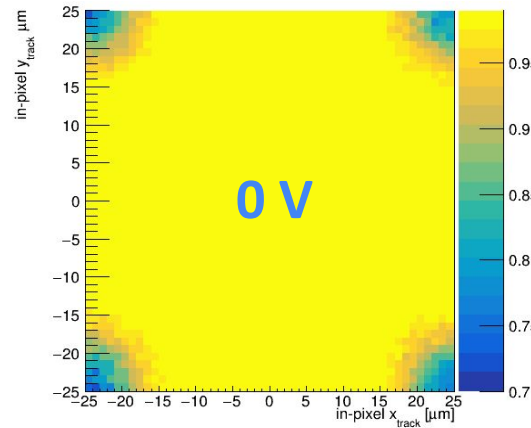


3D Pixel cell local efficiency before irradiation

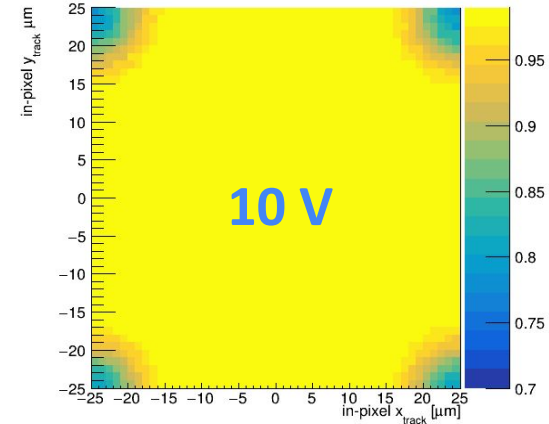
Pixel cell local efficiency map (normal incidence)

- **Central area:** higher than **99% efficiency**
- n^+ -columns are formed at a safety distance of $25\ \mu\text{m}$ from the handle wafer
 - **~99% efficiency at the N^+ column**

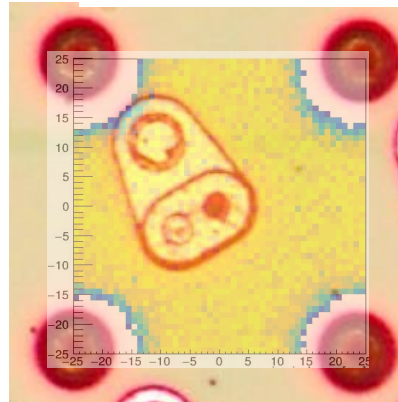
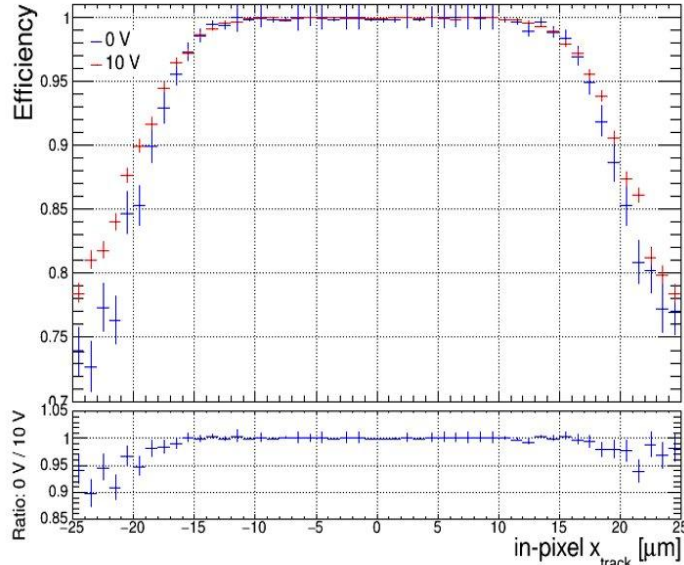
ATLAS ITk-Pixel



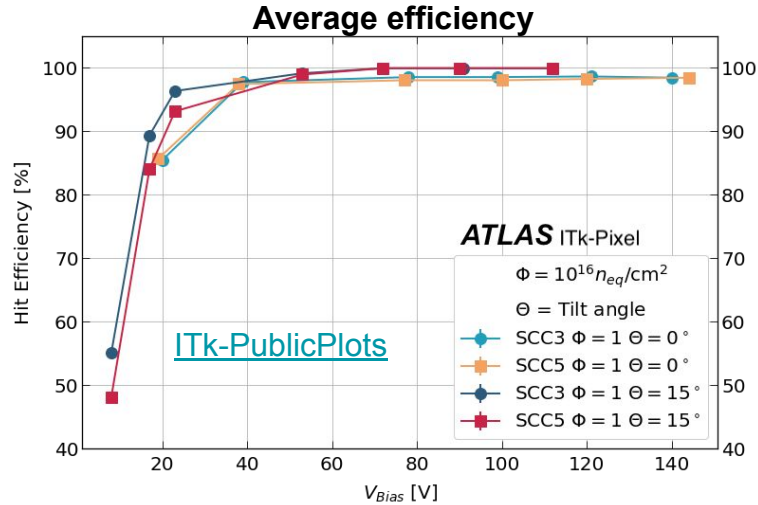
ATLAS ITk-Pixel



Projection of the top row of the maps



- **Lower efficiency zones visible in corners:**
 - Effect (75% – 99%) radius: $10\ \mu\text{m}$
 - p^+ columns max radius: $4\ \mu\text{m}$

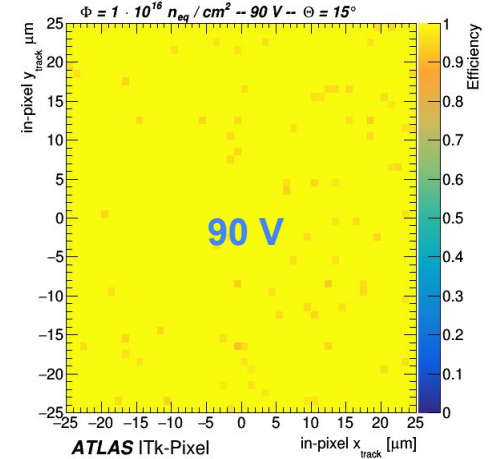
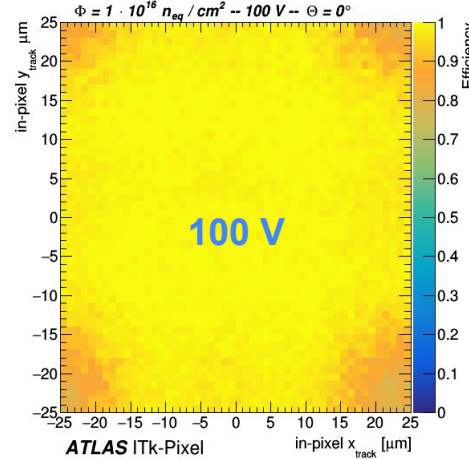


Pixel cell local efficiency maps

- For $\theta = 0^\circ$ results are similar to the one obtained before irradiation with **lower efficiency zones of radius $\sim 10 \mu m$ at the corner of the pixel cell**
- For $\theta = 15^\circ$ **lower efficiency areas are no longer visible in the local efficiency map** \rightarrow higher mean efficiency

Two modules irradiated in Bonn

- **Uniform fluence Φ of $1 \times 10^{16} n_{eq}/cm^2$**
- **Tested perpendicular ($\theta=0^\circ$) and tilted ($\theta=15^\circ$) w.r.t. the beam axis**
- **Average efficiency $> 97\%$ @ 40V bias**
- **FE average threshold of 1000 e**

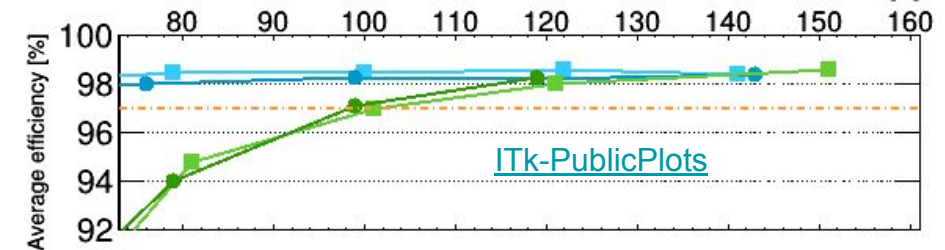
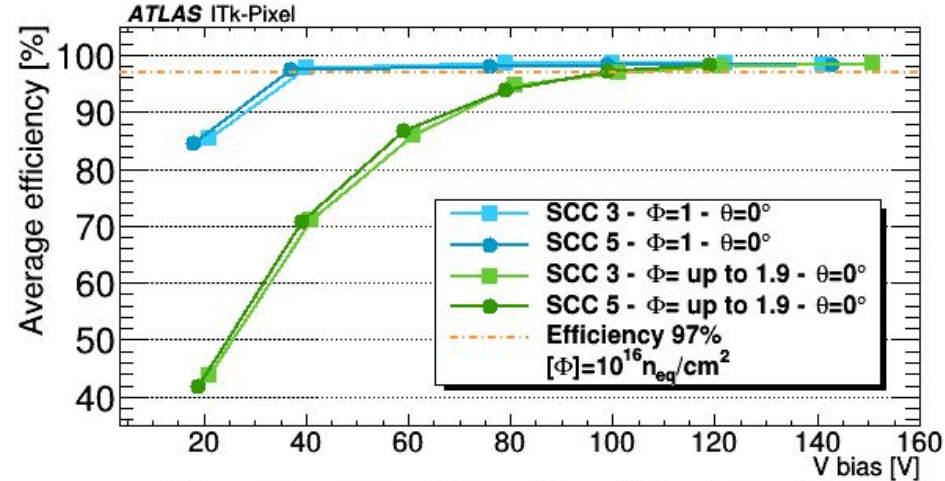
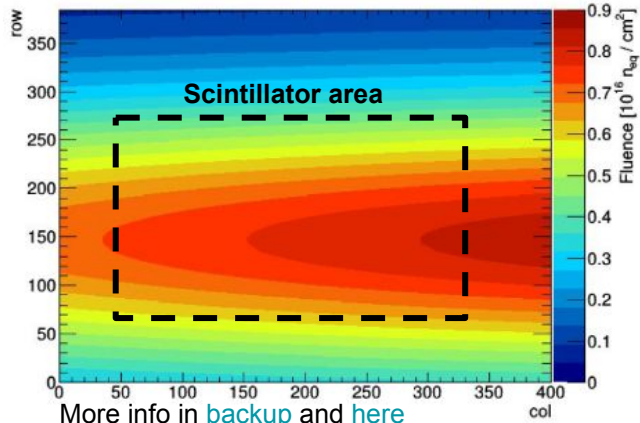


Beam tests after 2nd irradiation

Second irradiation at CERN IRRAD facility for the two modules irradiated in Bonn

- Not uniform fluence Φ up to $1.9 \times 10^{16} \text{ n}_{\text{eq}}/\text{cm}^2$
 - Over the TB scintillator area the mean fluence is $1.71 \times 10^{16} \text{ n}_{\text{eq}}/\text{cm}^2$ with a 3% uncertainty
- Tested perpendicular ($\theta=0^\circ$)
- Average efficiency **$\sim 97\%$ @ 100V bias**
- FE average threshold of 1000 e

IRRAD Reconstructed fluence map



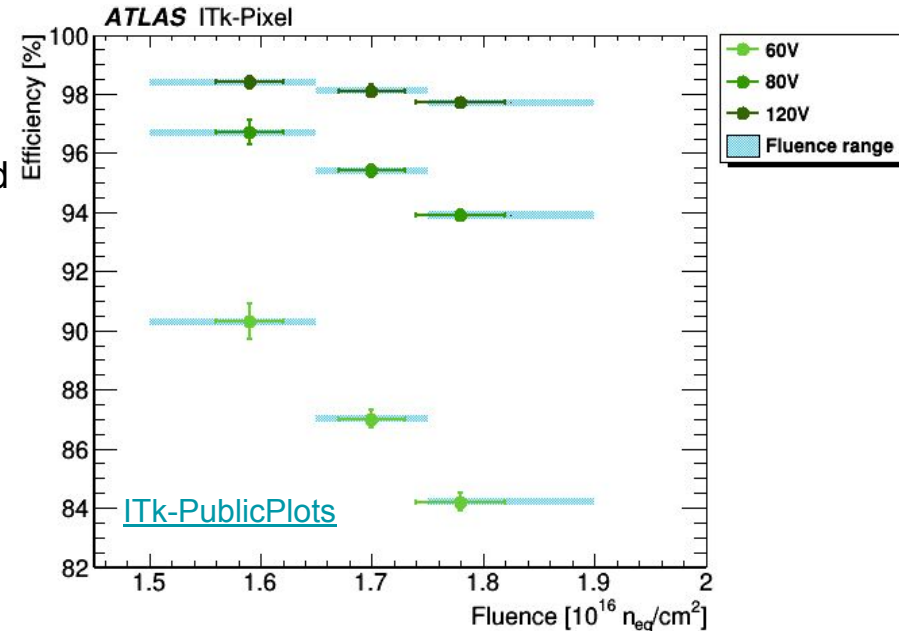
Average efficiency over the area covered by the TB scintillators

Efficiency vs Fluence (2nd irradiation)

Using the reconstructed fluence map of [slide11](#)

- Able to **assign a received fluence value to each pixel**
- Pixels are grouped in three fluence ranges (**light blue boxes**) according to the fluence Φ received
- **For each fluence range the average fluence is calculated (3% uncertainty)**
- **Lower efficiency at same bias voltage with increasing fluence, as expected**

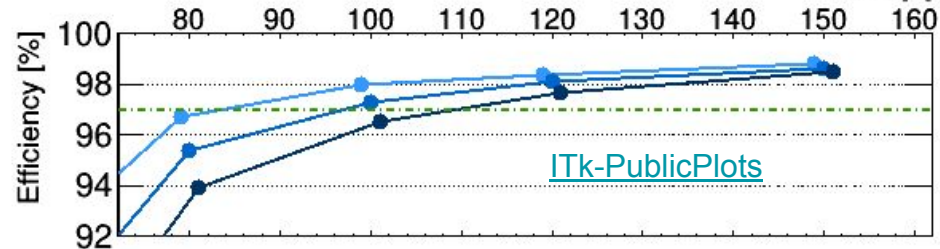
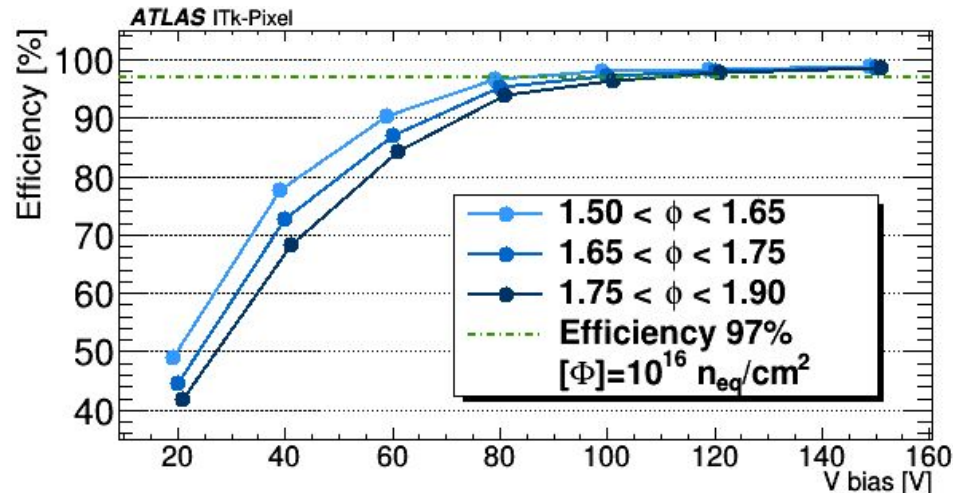
Fluence range [$10^{16} n_{eq}/cm^2$]	Average fluence [$10^{16} n_{eq}/cm^2$]
$1.5 < \Phi < 1.65$	1.59
$1.65 < \Phi < 1.75$	1.70
$1.75 < \Phi < 1.9$	1.78



Efficiency vs Fluence (2nd irradiation)

- In the three different fluence range **efficiency > 97%** is reached
 - at ~ 80 V for $\langle \Phi \rangle \approx 1.59$
 - at ~ 100 V for $\langle \Phi \rangle \approx 1.70$
 - at ~ 110 V for $\langle \Phi \rangle \approx 1.78$

Fluence range $[10^{16} n_{eq}/cm^2]$	Average fluence $[10^{16} n_{eq}/cm^2]$
$1.5 < \Phi < 1.65$	1.59
$1.65 < \Phi < 1.75$	1.70
$1.75 < \Phi < 1.9$	1.78

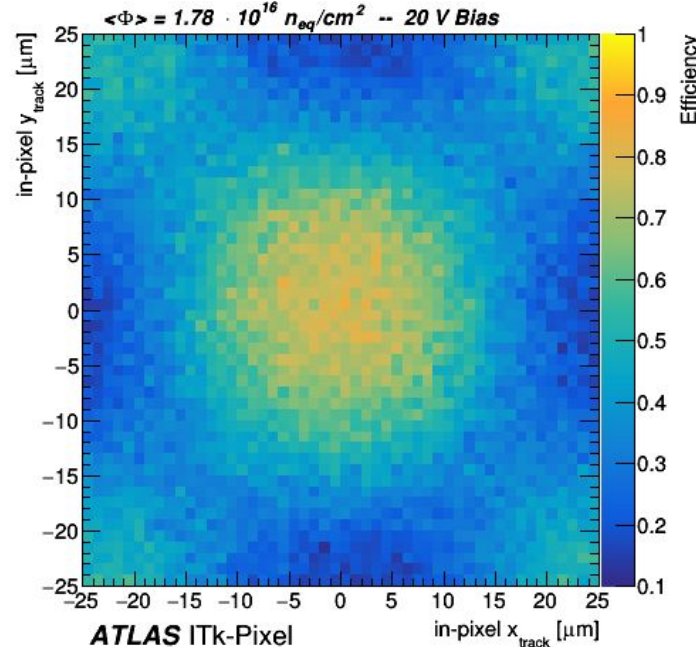
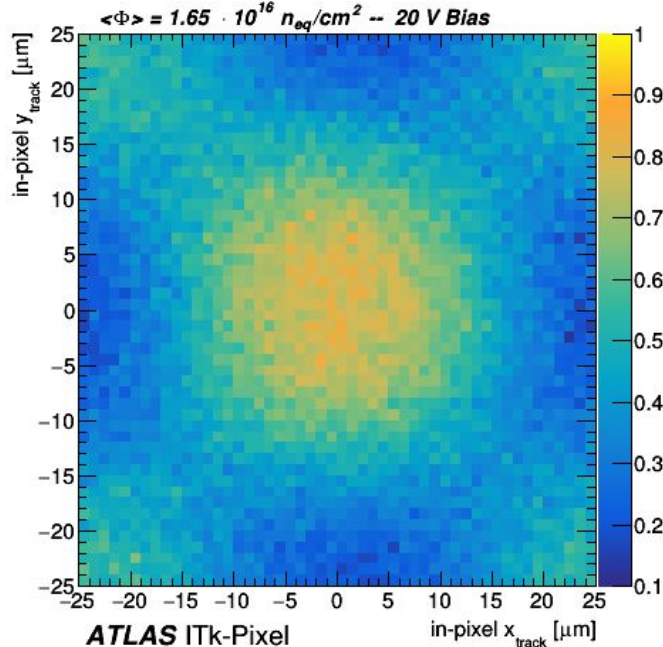


3D Pixel local efficiency after 2nd irradiation - 20V

At this stage pixels were grouped in two intervals based on the fluence received to increase statistics

Normal incidence

Fluence range [$10^{16} n_{eq}/cm^2$]	Average fluence
$1.5 < \Phi < 1.75$	$1.65 \times 10^{16} n_{eq}/cm^2$
$1.75 < \Phi < 1.9$	$1.78 \times 10^{16} n_{eq}/cm^2$



Lower efficiency areas

- Region with low electric field (simulation in [backup](#))
- Areas where the electrodes are implanted

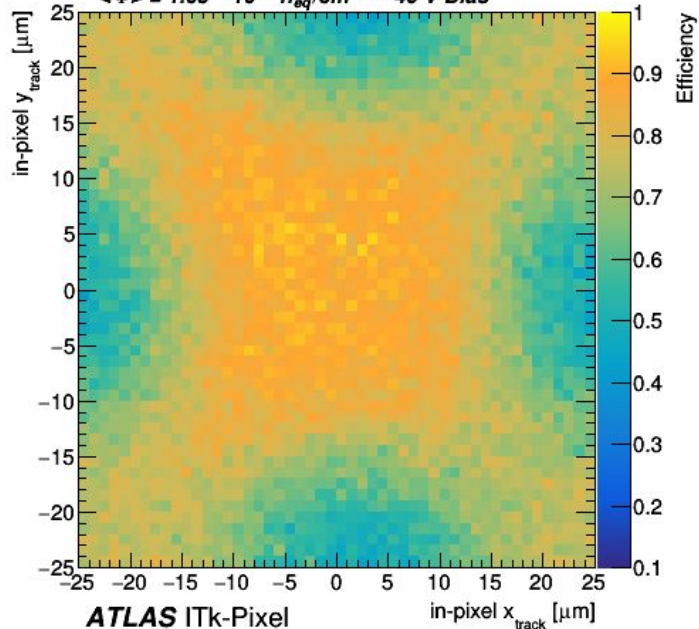
3D Pixel local efficiency after 2nd irradiation - 40V

At this stage pixels were grouped in two intervals based on the fluence received to increase statistics

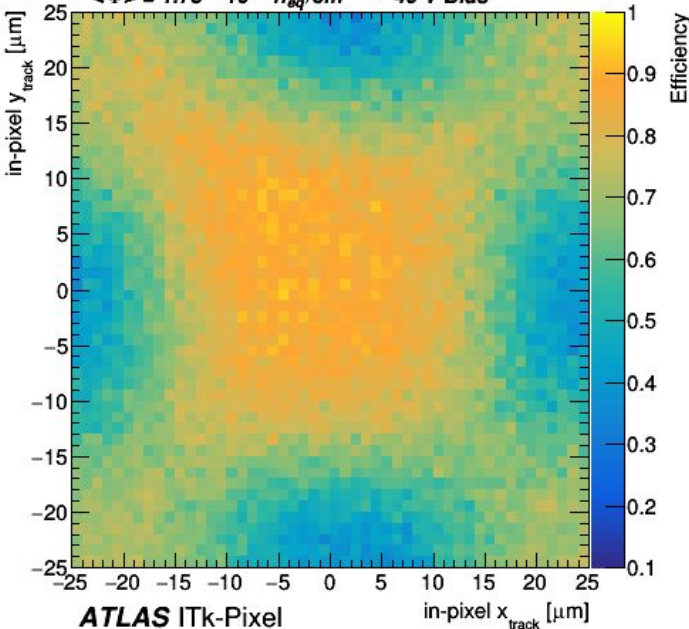
Fluence range [$10^{16} n_{eq}/cm^2$]	Average fluence
$1.5 < \Phi < 1.75$	$1.65 \times 10^{16} n_{eq}/cm^2$
$1.75 < \Phi < 1.9$	$1.78 \times 10^{16} n_{eq}/cm^2$

Normal incidence

$\langle \Phi \rangle = 1.65 \cdot 10^{16} n_{eq}/cm^2$ -- 40 V Bias



$\langle \Phi \rangle = 1.78 \cdot 10^{16} n_{eq}/cm^2$ -- 40 V Bias



Lower efficiency areas

- Region with low electric field (simulation in [backup](#))
- Areas where the electrodes are implanted

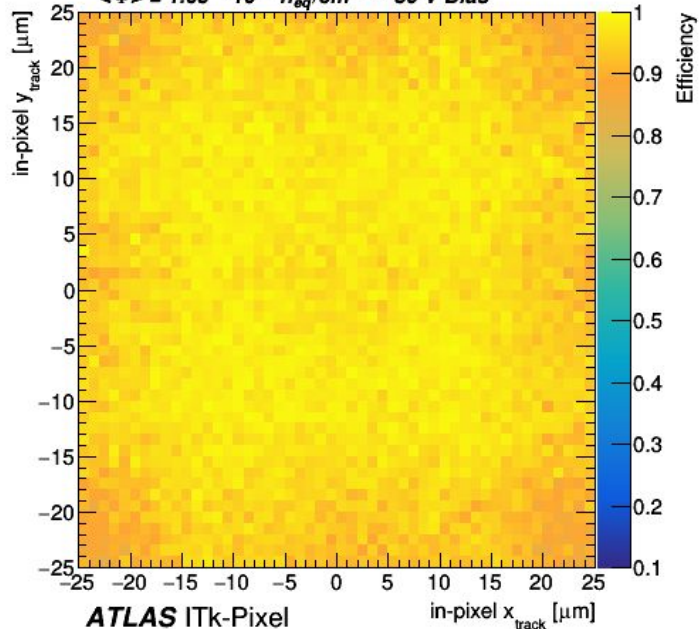
3D Pixel local efficiency after 2nd irradiation - 80V

At this stage pixels were grouped in two intervals based on the fluence received to increase statistics

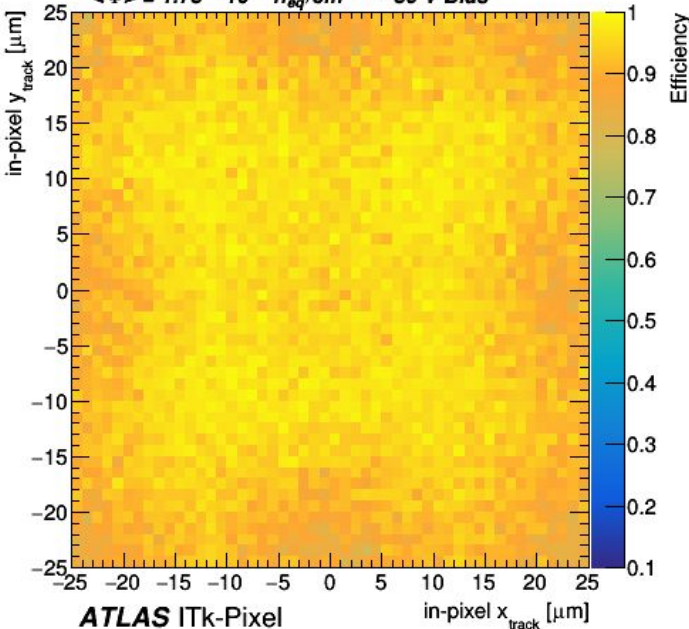
Fluence range [$10^{16} n_{eq}/cm^2$]	Average fluence
$1.5 < \Phi < 1.75$	$1.65 \times 10^{16} n_{eq}/cm^2$
$1.75 < \Phi < 1.9$	$1.78 \times 10^{16} n_{eq}/cm^2$

Normal incidence

$\langle \Phi \rangle = 1.65 \cdot 10^{16} n_{eq}/cm^2$ -- 80 V Bias



$\langle \Phi \rangle = 1.78 \cdot 10^{16} n_{eq}/cm^2$ -- 80 V Bias



Lower efficiency areas

- Region with low electric field (simulation in [backup](#))
- Areas where the electrodes are implanted

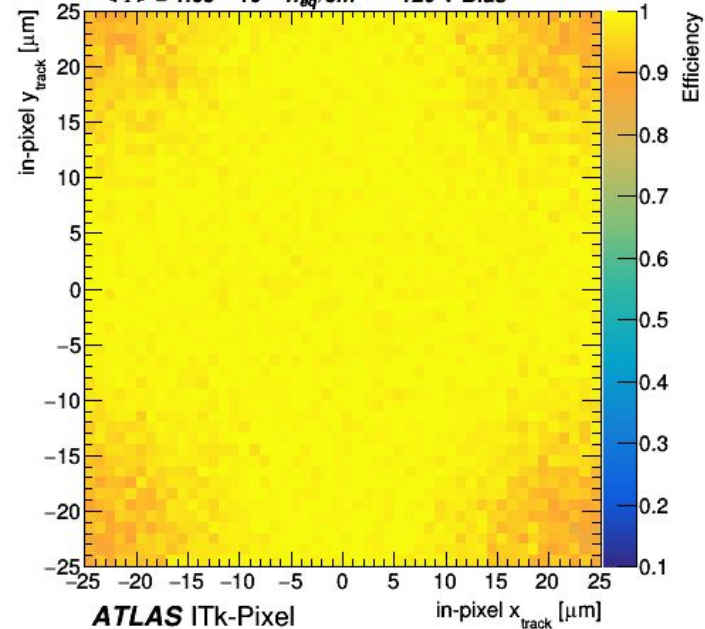
3D Pixel local efficiency after 2nd irradiation - 120V

At this stage pixels were grouped in two intervals based on the fluence received to increase statistics

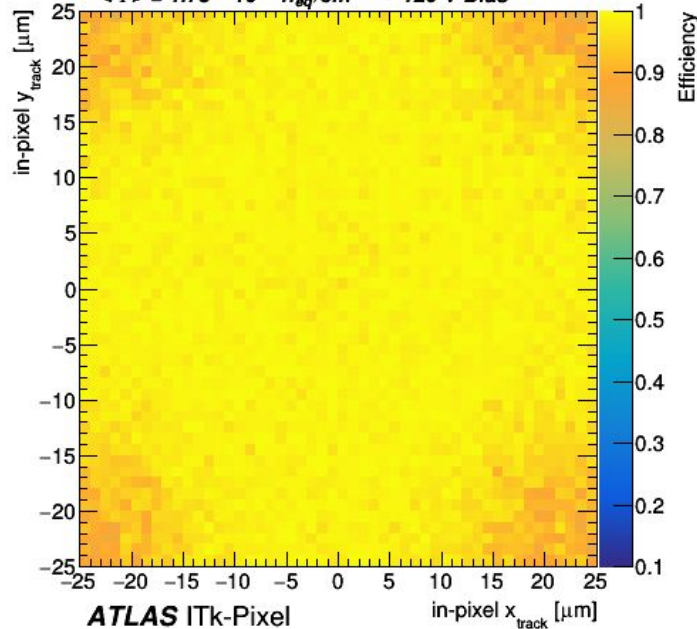
Fluence range [10 ¹⁶ n _{eq} /cm ²]	Average fluence
1.5 < Φ < 1.75	1.65 x 10 ¹⁶ n _{eq} /cm ²
1.75 < Φ < 1.9	1.78 x 10 ¹⁶ n _{eq} /cm ²

Normal incidence

$\langle \Phi \rangle = 1.65 \cdot 10^{16}$ n_{eq}/cm² -- 120 V Bias



$\langle \Phi \rangle = 1.78 \cdot 10^{16}$ n_{eq}/cm² -- 120 V Bias



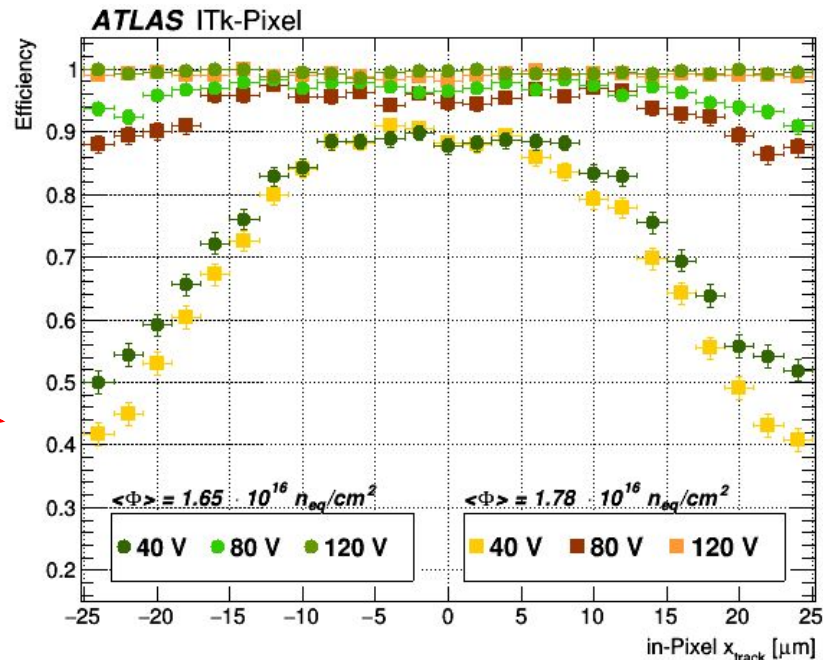
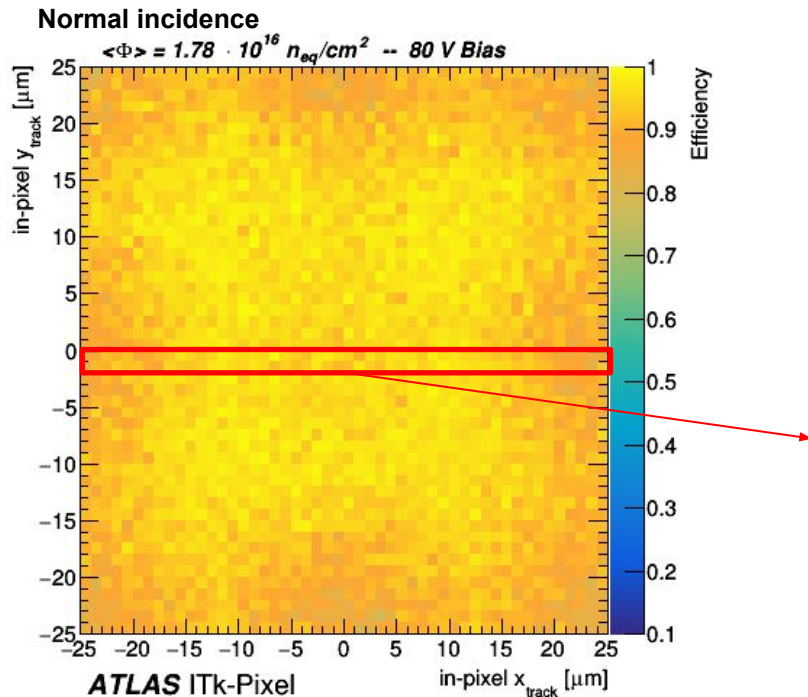
Lower efficiency areas

- Region with low electric field (simulation in [backup](#))
- Areas where the electrodes are implanted

Irradiated 3D pixel cell efficiency projections

Projection of the central row of the local efficiency map for different bias Voltages and fluences

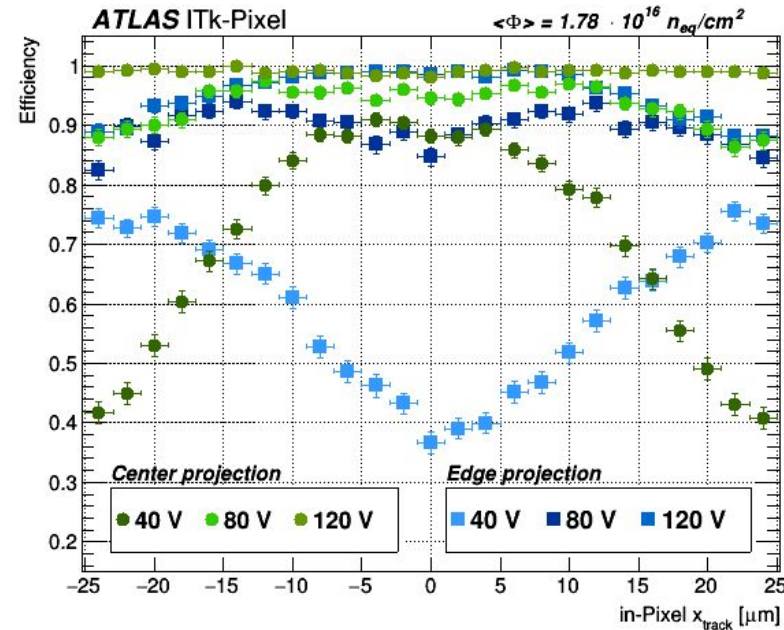
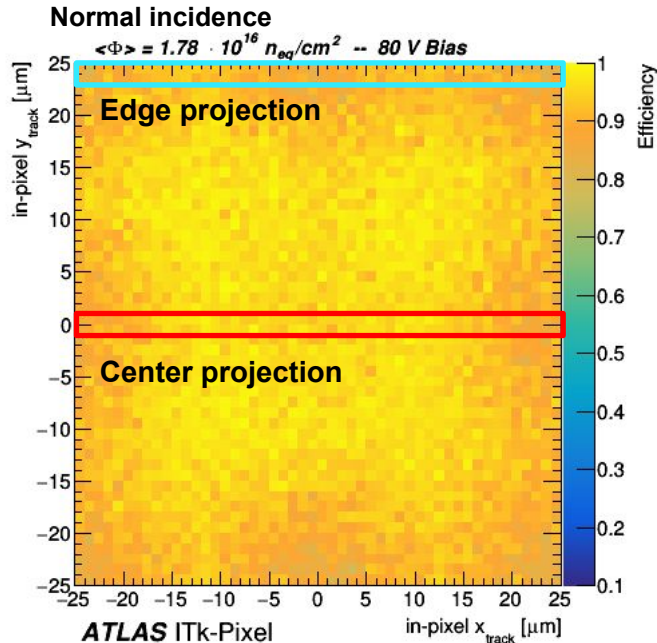
- Efficiency is lower for pixels which received higher fluence
- At 120V Bias no significant differences between the two fluence ranges
- At low bias (< 120 V) partial inefficiency in the middle of the cell (n^+ column)



Irradiated 3D pixel cell efficiency projections

Projection of the central and top rows of the local efficiency map for different bias Voltages

- In the edge projection **lower efficiency areas are visible in corners** (p^+ columns) also at 120 V
- At **120 V Bias** the **central region is fully depleted**
- The **lower efficiency in the middle of the edge** is related to a **lower electric field** in this region



Conclusions & Summary

The ATLAS ITk detector will be equipped with 3D sensor modules in the innermost layer (33-34 mm from collisions)

- Max fluence = $1.9 \cdot 10^{16} n_{eq}/cm^2$ (1.5 safety factor)
- Max TID = 1 Grad

3D modules (ITkPixV1.1 + 3D FBK $50 \times 50 \mu m^2$) assembled in Genova presented

- Tested unirradiated in laboratory (X-rays) and in test beams (CERN PS and SPS)
 - Efficiency > 98% already at 0 V bias
 - In-pixel efficiency in central area >99% efficiency
 - Lower in-pixel efficiency zones visible in corners
- Irradiated **up to $1.9 \times 10^{16} n_{eq}/cm^2$** (not uniform, @Bonn and IRRAD) and tested in test beams (CERN SPS)
 - Average efficiency >97% reached at ~80 V, ~100 V, ~110 V for average fluence $\approx 1.59 \Phi$, 1.70Φ , 1.78Φ resp.
 - Visible effect of p^+ columns: lower in-pixel efficiency in corners \rightarrow no longer visible if DUTs are tilted w.r.t the beam direction
 - The pixel cell is fully depleted with a bias voltage of about 150 V

Outlooks

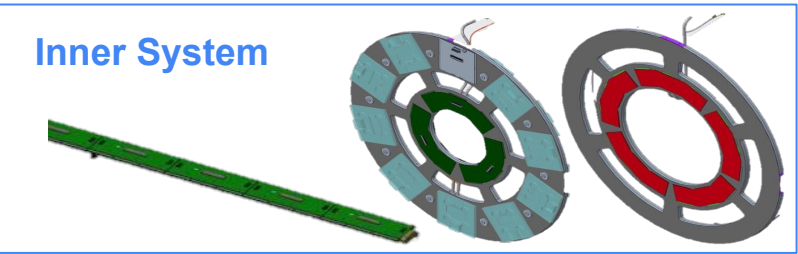
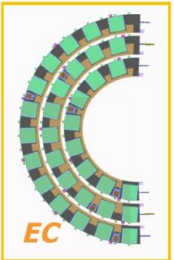
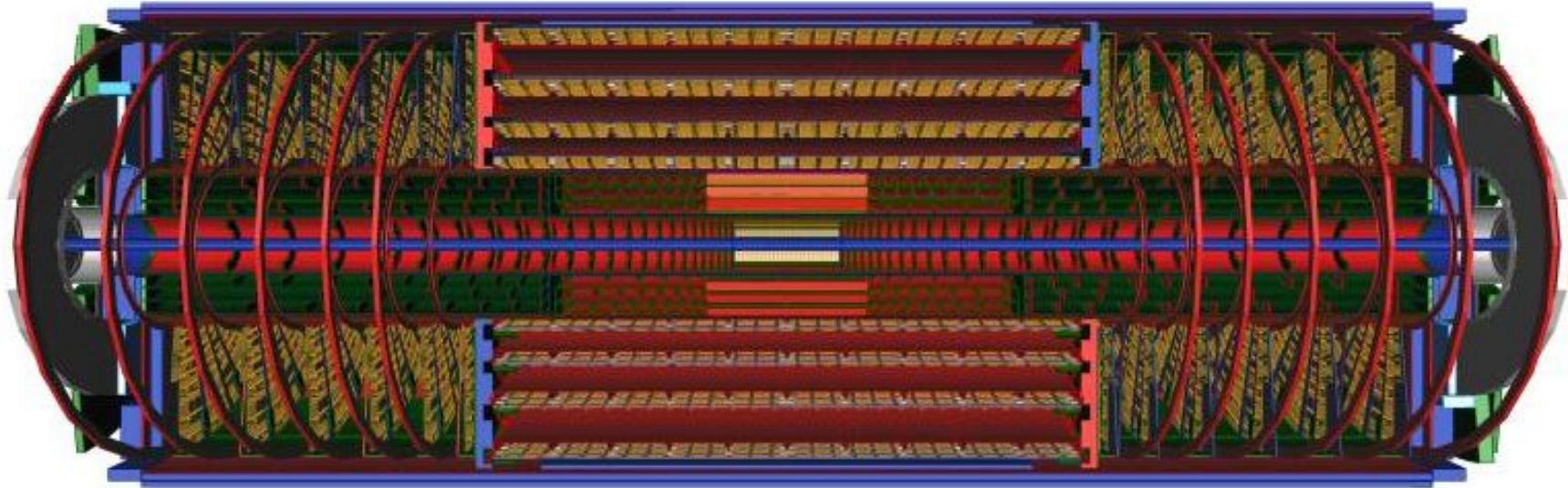
- Studies ongoing to investigate pixels that became noisy during data taking in these sensors

Thank you for the attention !

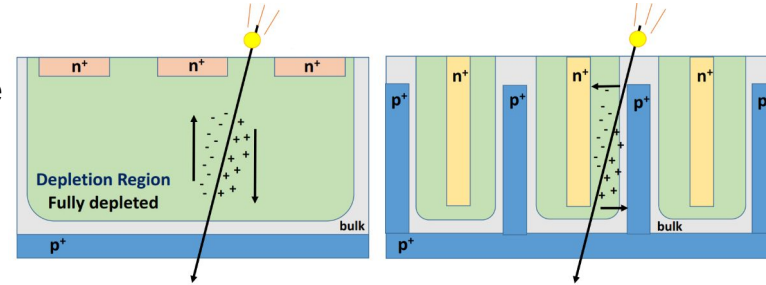
Acknowledgements to:

M.Bomben, T.I.Carcone, P.M.Chabrilat, A.Cordeiro, Y.A.R. Khwaira, C.Krause, K.Nakkalil, A.R.Petri, A.Skaf, S.Terzo, Y.Tian , P.Wolf, H.Ye and G.Pezzullo, F.Ravotti, M.Jaekel

Backup



- **Planar sensor:** standard pixel technology, n+ implants on p bulk surface
- **3D sensor:** n+ and p+ columns implanted vertically in p bulk substrate
 - Reduced distance between electrodes □ Shorter path of e/h
 - Lower impact of charge trapping along charge carrier path
 - Improved radiation hardness: perfectly OK @ $1e16 n_{eq}/cm^2$ NIEL
 - Lower depletion voltage □ Lower power dissipation after irradiation

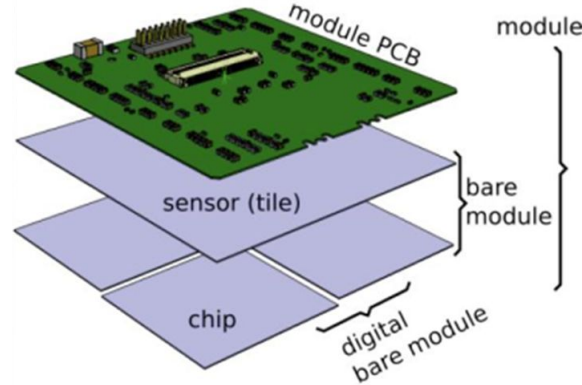


Planar sensors arranged in quad-modules: 1 bare module (4 chips + 1 planar sensor) + 1 flexible PCB

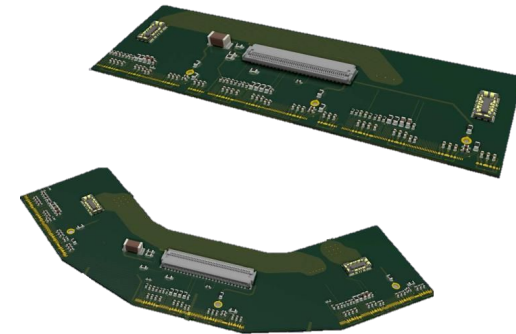
3D sensors arranged in triplet modules: 3 bare modules (1 chip + 3D sensor) + 1 flexible PCB

- Both ring and barrel triplet assembly exercised with RD53A prototypes

Quad-module stack-up



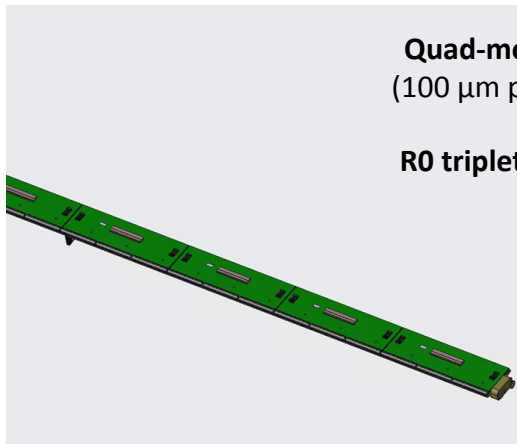
Ring and barrel triplet module flexible PCB



Barrel (stave)

L0: 96 triplets

12 staves x 8 triplets



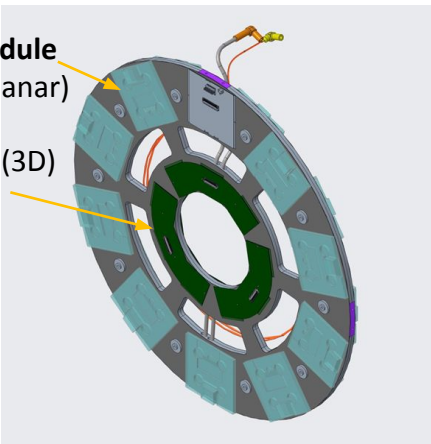
Endcap (rings)

R0: 180 triplets

30 rings x 6 triplets

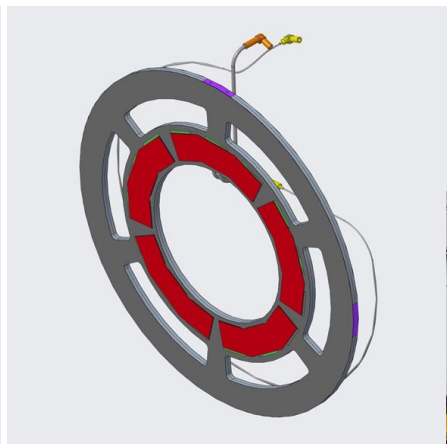
Quad-module
(100 μm planar)

R0 triplet (3D)

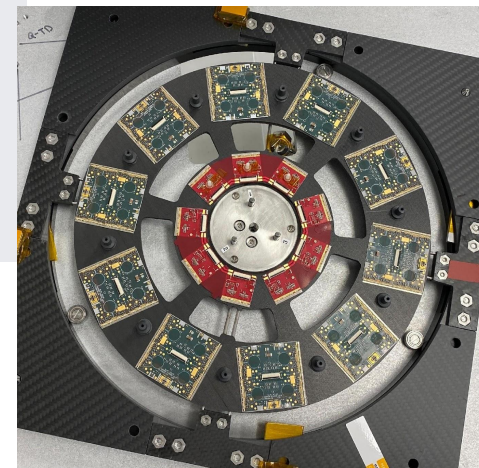


R0.5: 120 triplets

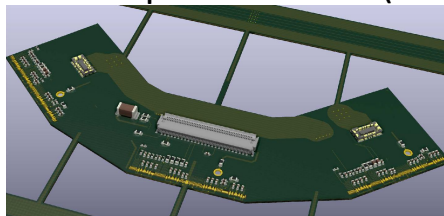
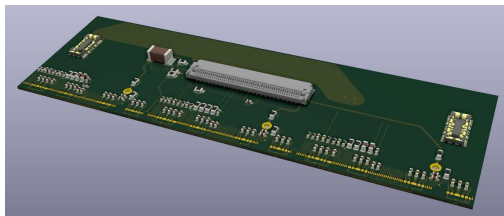
12 rings x 10 triplets



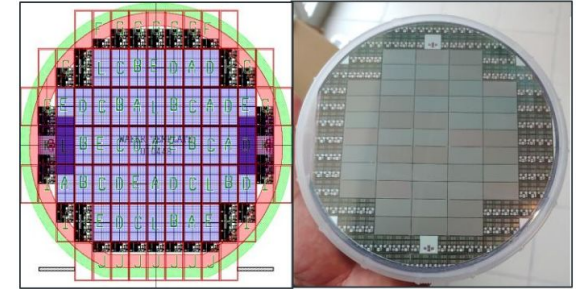
**Prototype of
ITk R0 ring with
RD53A modules:
10 quad-modules
3 R0 triplets**



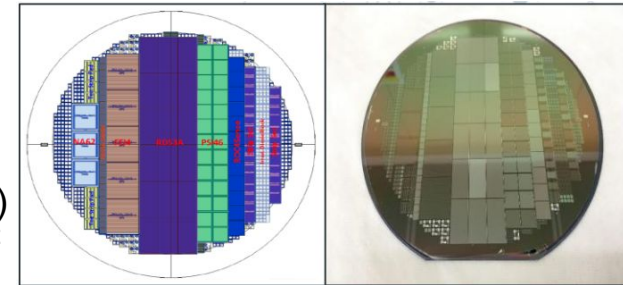
- 3D sensors will be assembled in triplet modules (1 flex + 3 bare modules)



- 2 different pixel cell dimensions for the 3D sensors (2x2 cm² pieces):
 - 25x100 μm² in the barrel triplet modules (288 sensors needed)
 - 50x50 μm² in the endcap triplet modules (900 sensors needed)
- In the last years, several R&D production of wafers by FBK:
 - Sensors 1x2 cm² compatible with the RD53A chip
 - Batch 2: Mask aligner, 130 μm active thickness
 - Batch 3: Stepper, 150 μm active thickness
 - Details at: [S. Terzo et al 2021 Front. Phys. 9:624668](#)
 - Bare modules (3D sensor + RD53A chip) assembled on card (SCC)
 - Tested before and after irradiation at DESY, up to 1e16 n_{eq}/cm²
 - Details at: [Md.A.A. Samy et al 2021 JINST 16 C12028](#)



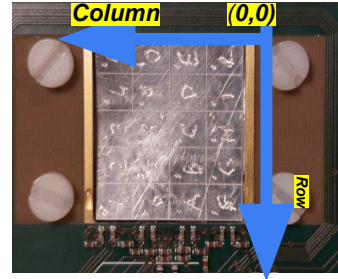
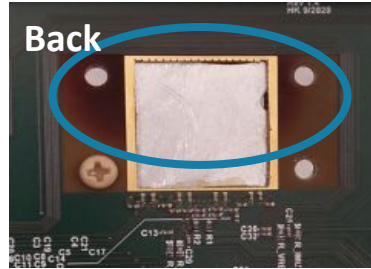
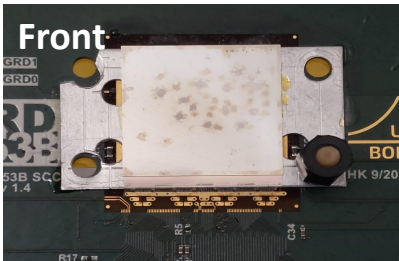
3rd 3D-SS batch also “New RD53A” ROCs
With Stepper Lithography Technique



2nd 3D-SS batch also “New RD53A” ROCs
With Mask Aligner Lithography Technique

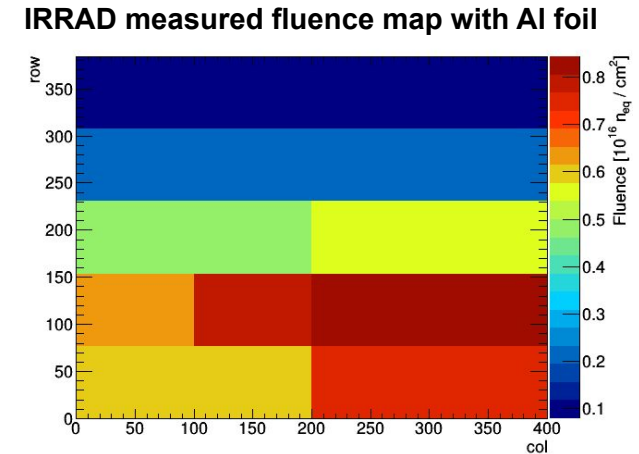
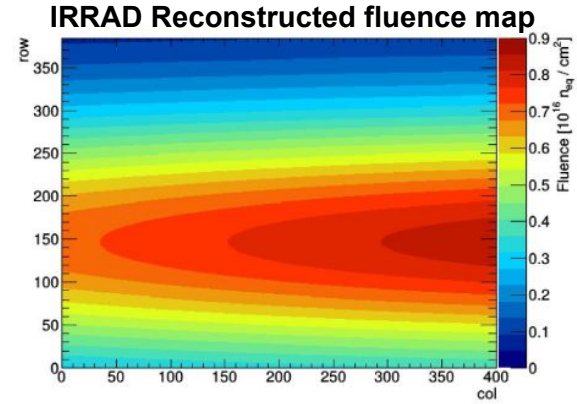
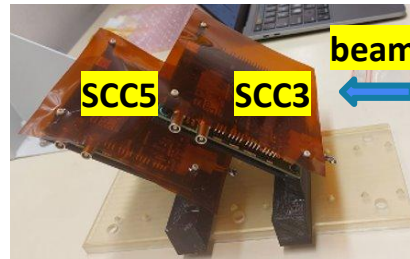
Modules 2nd irradiations at IRRAD

- at IRRAD (CERN, 7-27 September 2022) to add to fluence (not uniform)
 $0.9 \times 10^{16} n_{eq}/cm^2$ (peak), $0.5 \times 10^{16} n_{eq}/cm^2$ average
- devices inclined to increase irradiated area, scanning horizontally
 - quite uniform irradiation along x, gaussian along y (beam profile)
- Visual inspection: visible dark shape in a $\sim 1 \times 2$ cm² area, not vertically centered, dots on the sensor surface
- Received fluence (local and average) measured from the activation of Al dosimeters placed on the back of sensor



Total integrated fluence:

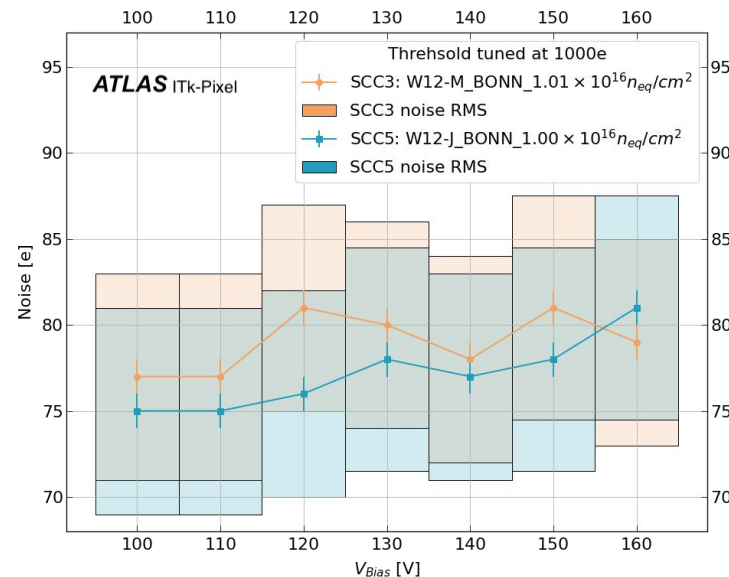
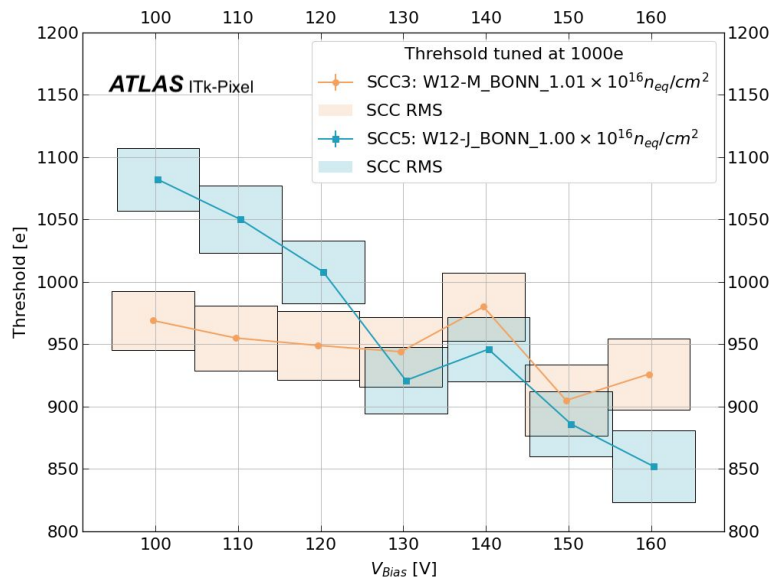
- **$1.9 \times 10^{16} n_{eq}/cm^2$ (peak)**
- **$1.5 \times 10^{16} n_{eq}/cm^2$ average**
- Not uniform fluence used to map **efficiency** measurements to **different fluence values**



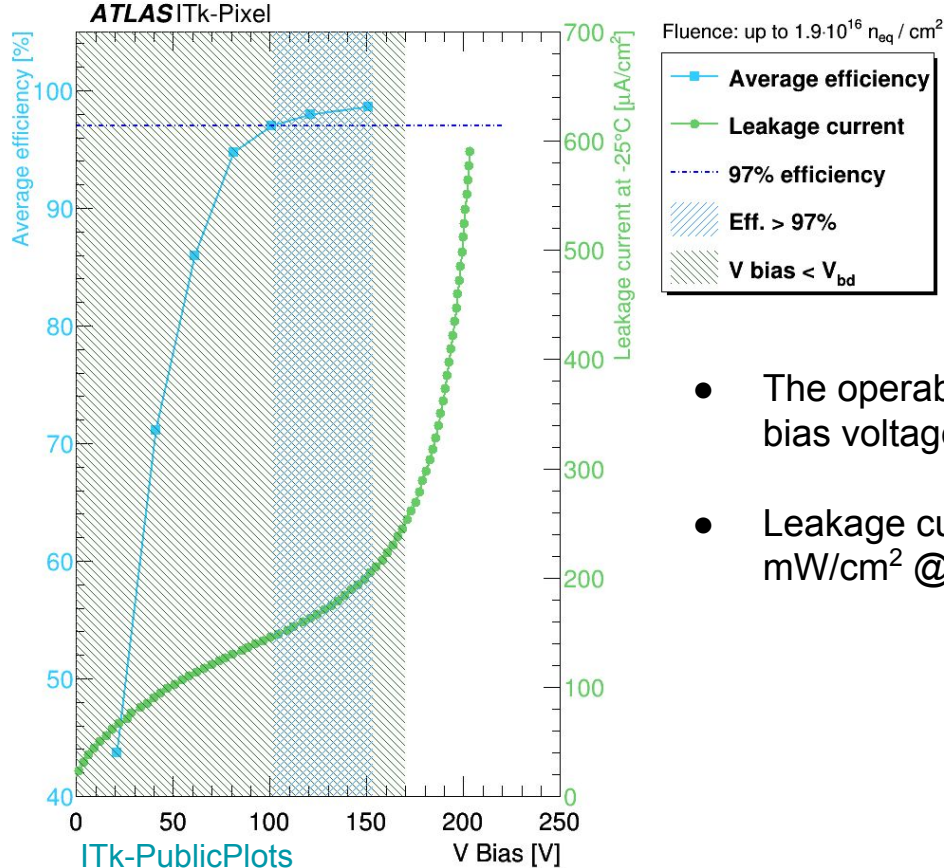
Tuning strategy and stability at TBs

- SCCs studied in test beams at CERN SPS after each irradiation
 - Strategy: tuned with target 1000e at 100V bias, same tuning used for all V_{bias}
 - Threshold and Noise distributions verified to be reasonably stable over a large V_{bias} range

[ITk-PublicPlots](#)



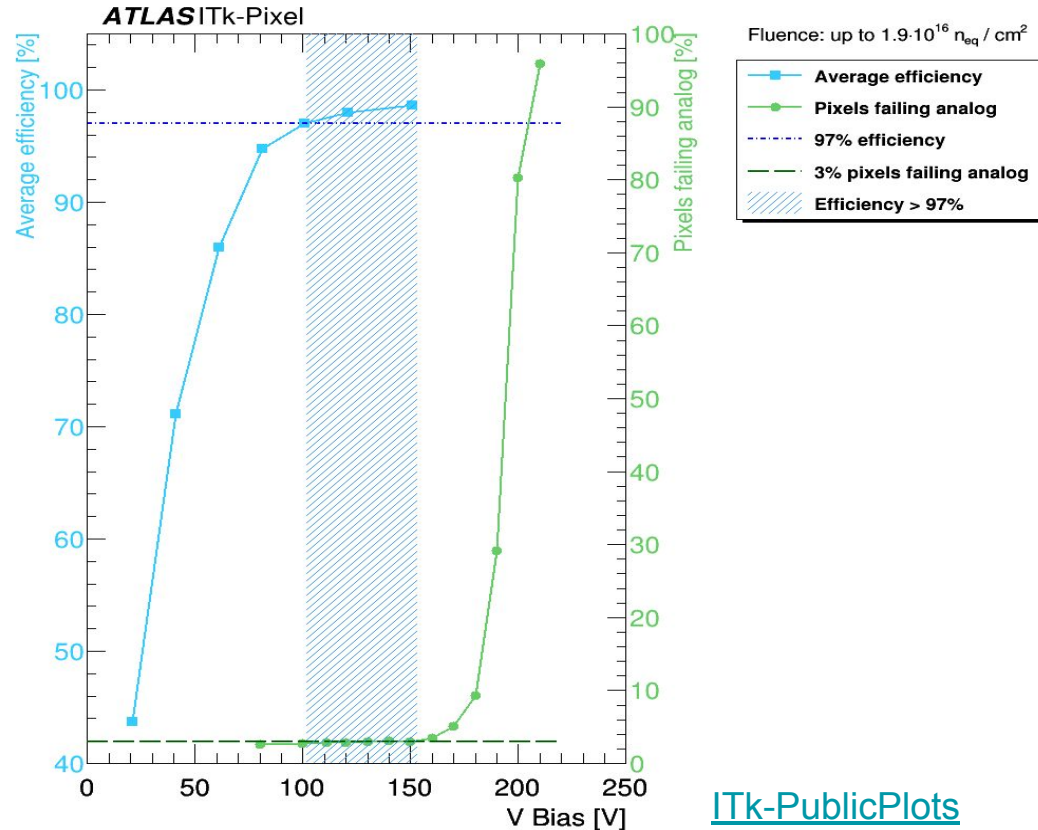
(Error bars are the distribution mean error, columns are the distribution standard deviation)
Plots with modules irradiated at 10¹⁶ n_{eq}/cm², similar results after second irradiation



- The operability window is defined by high efficiency (>97%) and bias voltage below the breakdown: ~100V to ~170V bias
- Leakage current $I \sim 150 \mu\text{A}/\text{cm}^2$ and power dissipation 15 mW/cm^2 @ 100 V bias (scaled at -25°C) for SCC3

Operability window

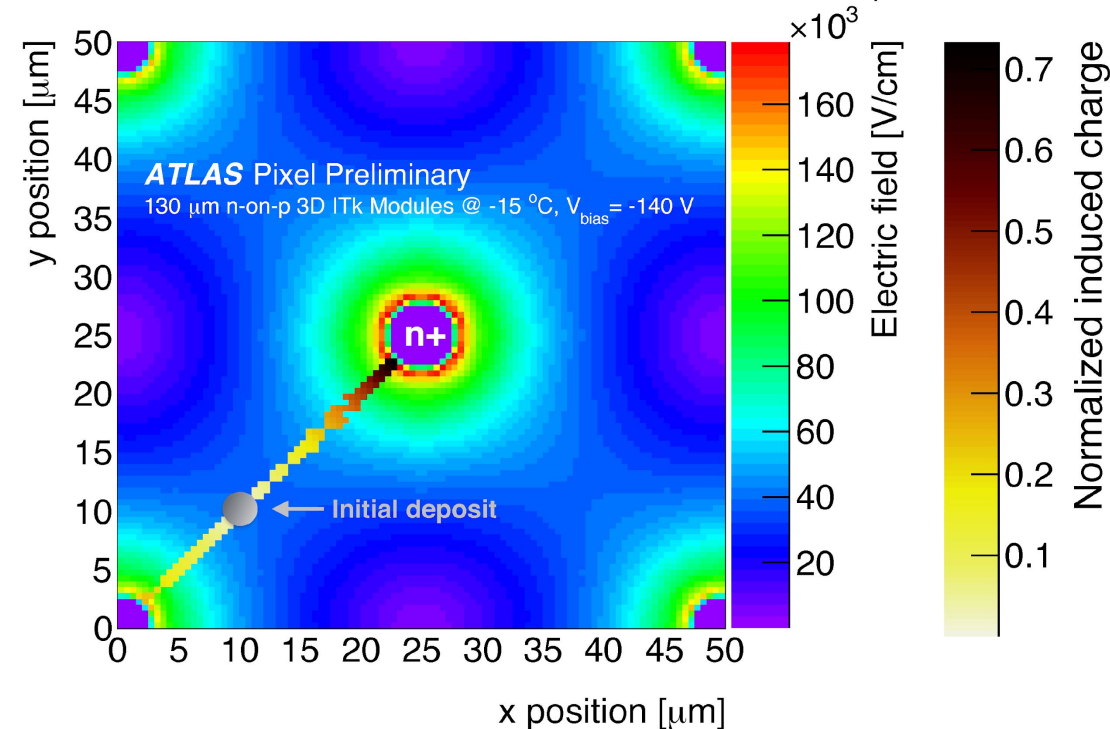
- Observed number of noisy / disabled pixels increasing at high voltages (>120V bias)
 - same tuning (1000e @ 100V bias) used for all V_{bias} may be reduced by tuning at each voltage under investigation
- performed **analog** scan vs V_{bias} to study the effect systematically
 - Slow increase at around ~3% failing pixels up to about ~150V bias
 - Faster rise next to breakdown voltage
 - Possibility to improve the 3% failing plateau under investigation
- The operability window is reasonably the overlap between the region at high efficiency and the region with low fraction of failing pixels: ~100V to ~160V bias in this example



Operability window

Simulated electric field after irradiation [more info: [ITk_Public_Plots](#)]

Charge carrier drift in E-field ($\Phi=10^{16} \text{ n}_{\text{eq}}/\text{cm}^2$)



In the plot represented field at $V = -140\text{V}$,
after $1 \times 10^{16} \text{ neq}/\text{cm}^2$

Lower electric field may be associated
with lower efficiency areas, at least at low
Voltage Bias ?

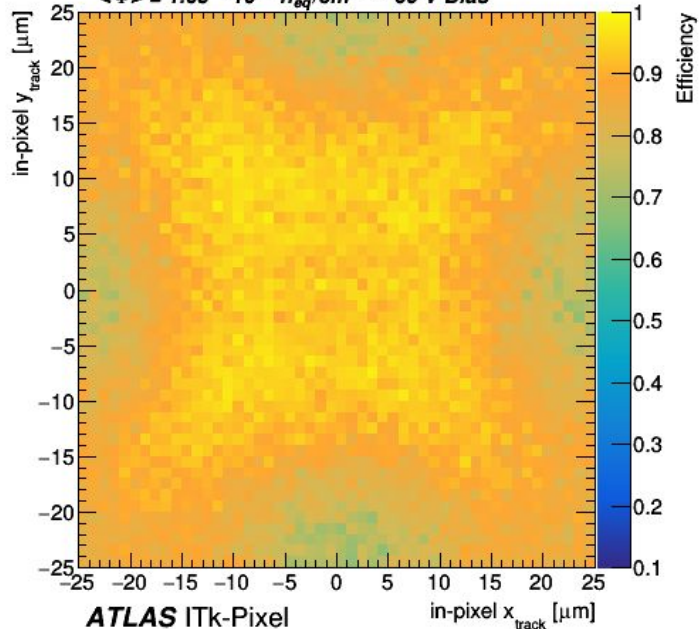
3D Pixel local efficiency after 2nd irradiation - 60V

At this stage pixels were grouped in two intervals based on the fluence received to increase statistics

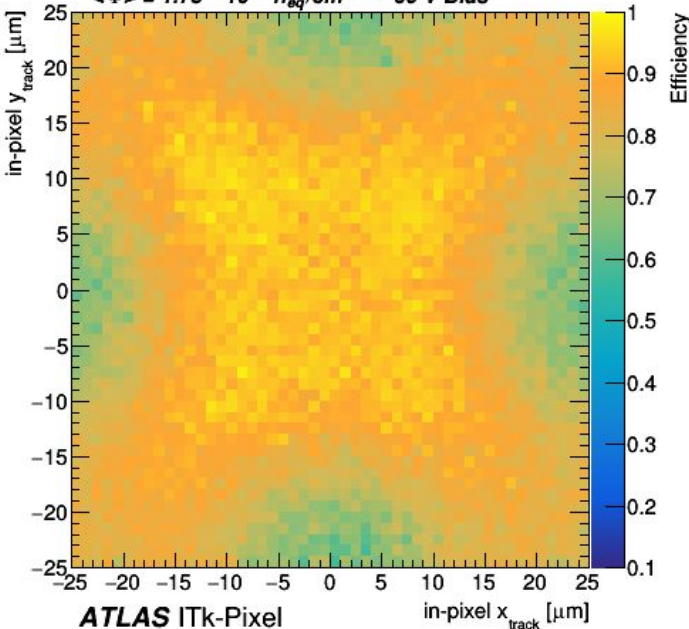
Fluence range [$10^{16} n_{eq}/cm^2$]	Average fluence
$1.5 < \Phi < 1.75$	$1.65 \times 10^{16} n_{eq}/cm^2$
$1.75 < \Phi < 1.9$	$1.78 \times 10^{16} n_{eq}/cm^2$

Normal incidence

$\langle \Phi \rangle = 1.65 \cdot 10^{16} n_{eq}/cm^2$ -- 60 V Bias



$\langle \Phi \rangle = 1.78 \cdot 10^{16} n_{eq}/cm^2$ -- 60 V Bias



Lower efficiency areas

- Region with low electric field (simulation in [backup](#))
- Areas where the electrodes are implanted

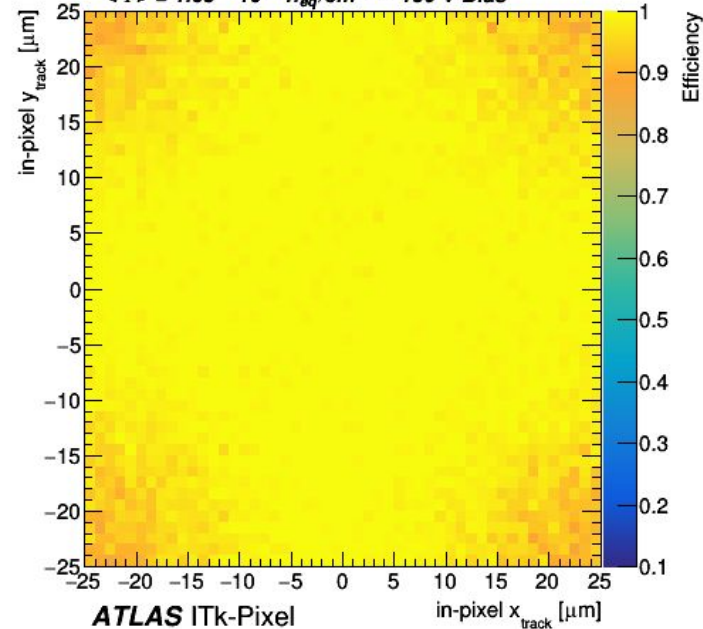
3D Pixel local efficiency after 2nd irradiation - 150V

At this stage pixels were grouped in two intervals based on the fluence received to increase statistics

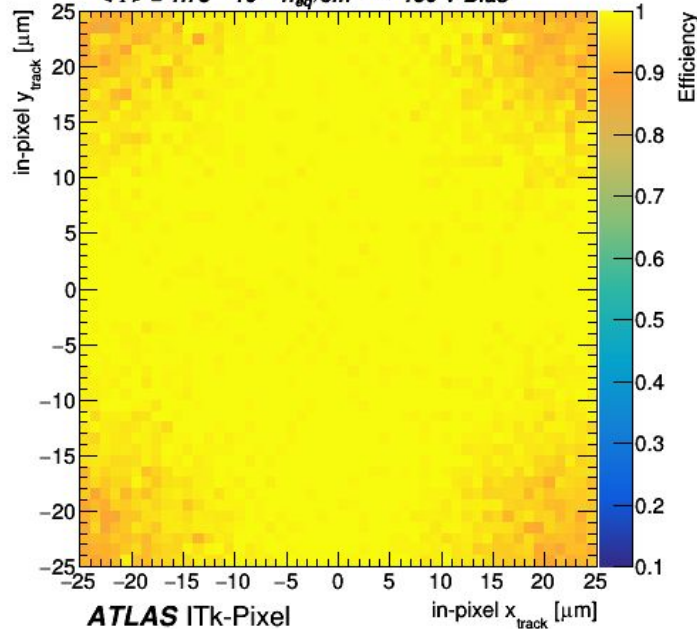
Fluence range [$10^{16} n_{eq}/cm^2$]	Average fluence
$1.5 < \Phi < 1.75$	$1.65 \times 10^{16} n_{eq}/cm^2$
$1.75 < \Phi < 1.9$	$1.78 \times 10^{16} n_{eq}/cm^2$

Normal incidence

$\langle \Phi \rangle = 1.65 \cdot 10^{16} n_{eq}/cm^2$ -- 150 V Bias



$\langle \Phi \rangle = 1.78 \cdot 10^{16} n_{eq}/cm^2$ -- 150 V Bias



Lower efficiency areas

- Region with low electric field (simulation in [backup](#))
- Areas where the electrodes are implanted